

Form PTO 1449 U.S. Department of Commerce Patent and Trademark Office Information Disclosure Statement by Applicant	ATTY. DOCKET NUMBER HITA.0120	SERIAL NUMBER 09/987,914
	APPLICANT OSHIMA et al.	
	FILING DATE November 16, 2001	GROUP -2814 2823

U.S. Patent Documents

Examiner Initial	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBC CLASS	FILING DATE

Foreign Patent Documents

Examiner Initial	DOCUMENT NUMBER	FILING DATE	COUNTRY	CLAS S	SUB- CLASS	TRANSLATION	
						YES	NO
QNB	8-316209	5/22/95	Japan	H01L	21/3068	Abstract	X
QNB	9-306988	4/11/96	Japan	H01L	21/768	Abstract	X

Other Documents (Including Author, Title, Date Pertinent Pages, Etc.)

QNB	"The Etching of Low-l Films - The keys to the application of organic films in Cu damascene structures are resistance to heating and to O ₂ -plasma", Semiconductor World 1998, pp. 74-76 (translation pp. 1-7)

EXAMINER <i>William M. Brewster</i>	DATE CONSIDERED <i>31 MAR 03</i>
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EXAMINER: Initial if citation is considered, whether or not citation is in conformance with MPEP 609; draw a line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant